



MARC 2023
Palacios Group - Pitch Presentations

January 20th, 2023

MATERIALS EXPO

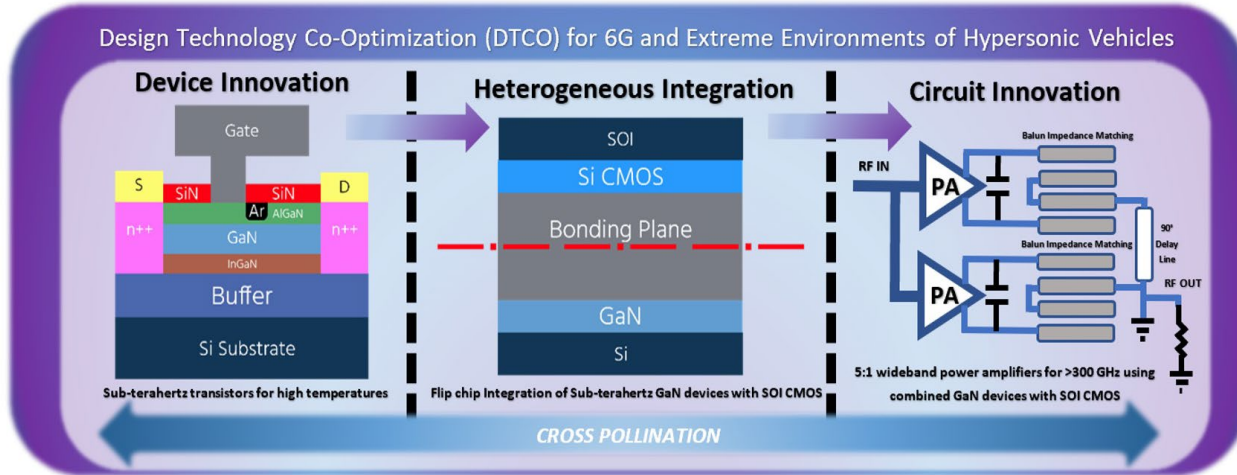
MARC 2023

Palacios Group - Pitch Presentations

1. [Pradyot Yadav](#)
2. [Qingyun Xie](#)
3. [Hae Won Lee](#)
4. [Pao-Chuan Shih](#)
5. [Jung-Han Hsia \(Sharon\)](#)
6. [David Morales](#)
7. [Gillian Micale](#)
8. [Jiadi Zhu](#)
9. [Minsik Oh](#)
10. [Joshua Perozek](#)
11. [Hridibrata Pal](#)
12. [John Niroula](#)

Heterogeneous Integration of GaN and Si for MMICs above 300 GHz, 6G Applications and Beyond

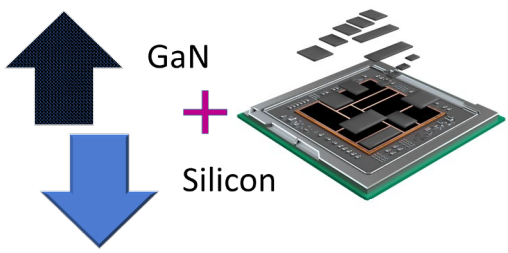
Pradyot Yadav, Q. Xie, J. Niroula, T. Palacios



Satellite



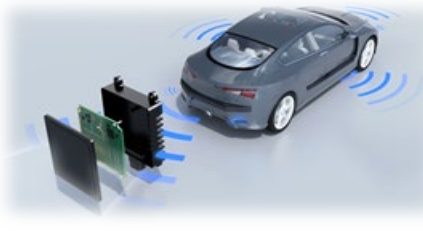
Radio Astronomy



Heterogeneous Integration



Security Screening



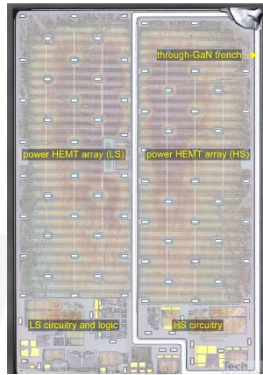
Automotive Radar



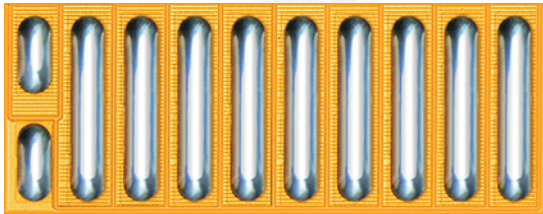
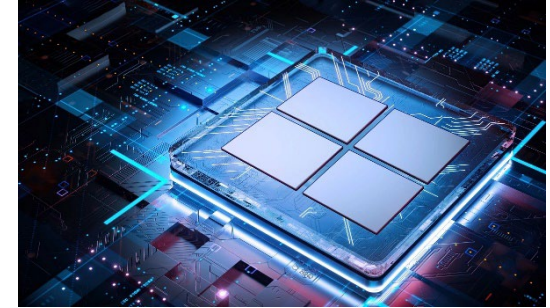
Cellular

Monolithically Integrated GaN Complementary Technology for All-GaN Multi-Functional Chips

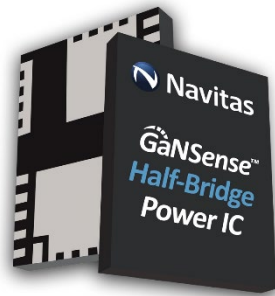
Qingyun Xie, N. Chowdhury, M. Yuan, J. Niroula, P. Yadav, T. Palacios



EPC
EPC2152
(2020)



2014



Navitas
NV6247
(2022)

intel®
Intel's Vision 2030
(IEDM2022)

**E-mode
transistor**

**Integrated circuits (half bridge and gate driver)
< 100 transistors**

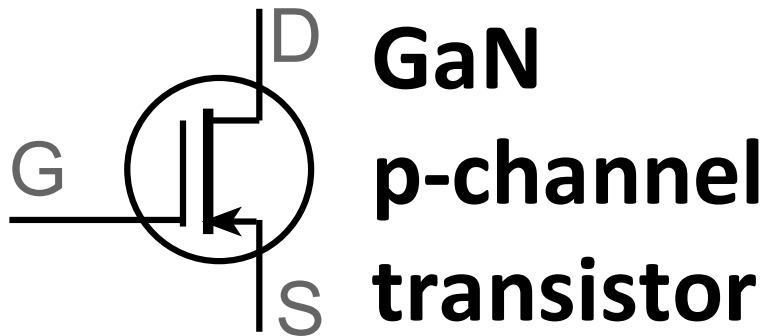
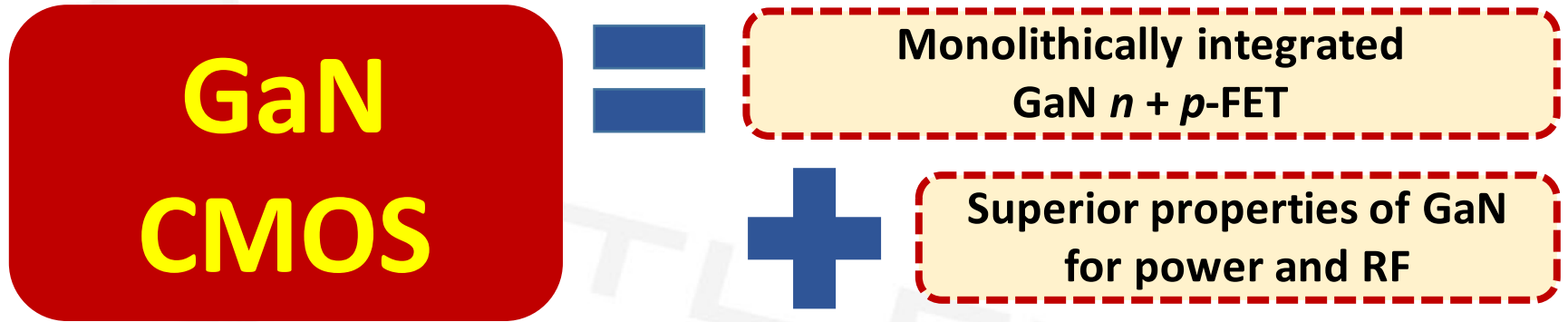
Acknowledgments:

Intel Corp. (027196-00001)
NASA (80NSSC17K0768)

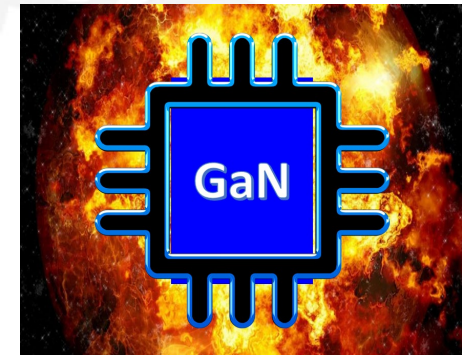
Samsung Electronics Co., Ltd. (033517-00001)
Qualcomm Inc. (MAS-492857)
ARPA-E (AR0001591)

Monolithically Integrated GaN Complementary Technology for All-GaN Multi-Functional Chips

Qingyun Xie, N. Chowdhury, M. Yuan, J. Niroula, P. Yadav, T. Palacios



Applications in power, analog mixed-signal



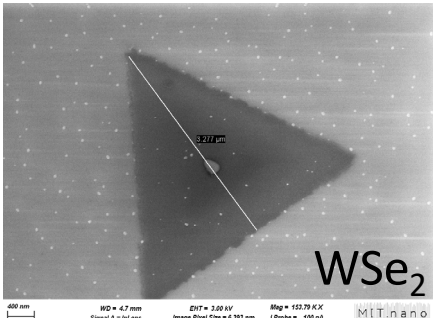
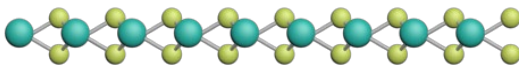
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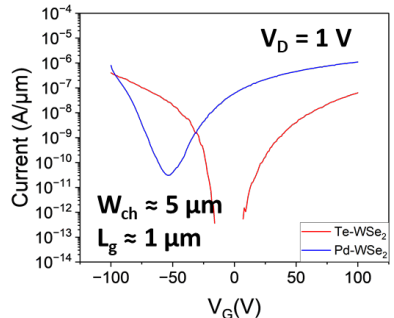
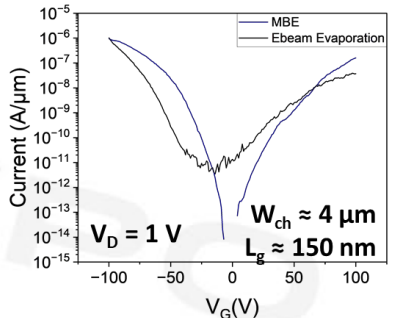
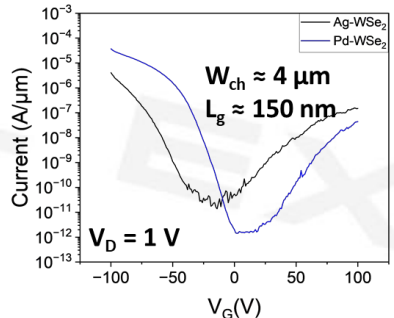
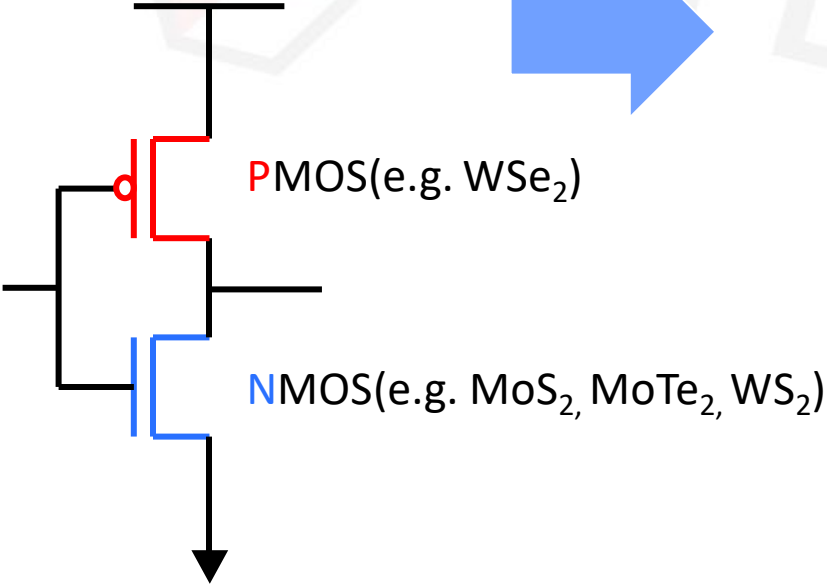
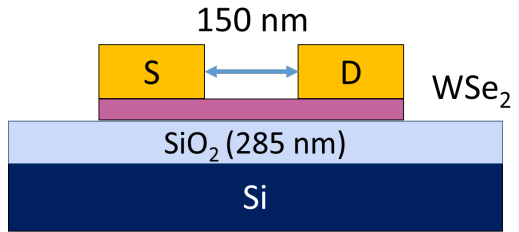
Samsung Electronics Co., Ltd. (033517-00001)
Qualcomm Inc. (MAS-492857)
ARPA-E (AR0001591)

High Performance P-type 2D Transistors with Low Resistance Contacts

Hae Won Lee, Jiadi Zhu, Ji-Hoon Park, Yasen Hou, Jagadeesh S. Moodera, Jing Kong and Tomás Palacios



P-type 2D device



- ✓ **Metals:** Ag, Pd, Te
- ✓ **Methods:** Ebeam evaporation, Molecular beam epitaxy

Uniform High-Aspect-Ratio GaN Vertical Sub-30-nm-Diameter Nanowires Formed by Optimized Two-Step Etching Process

Pao-Chuan Shih (pcshih@mit.edu) and Tomás Palacios

- **Climate change and extreme weathers**
- **Ecological crisis**

Unsustainable society

- Limited green energy
- Low energy efficiency

For our future

Sustainable society

- Green energy
- high efficiency

As EE engineers,
What can we do?

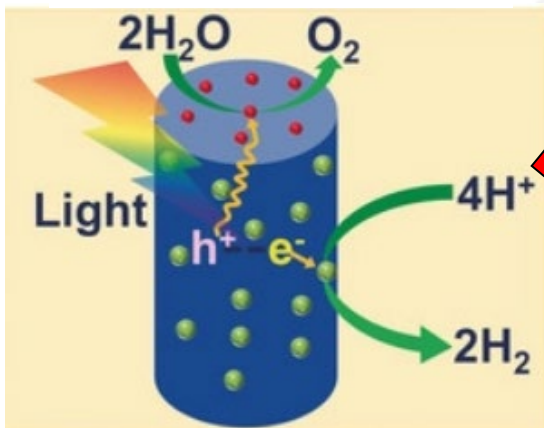
<https://seec-tonko.house.gov/taxonomy/issues/climate-change>

Uniform High-Aspect-Ratio GaN Vertical Sub-30-nm-Diameter Nanowires Formed by Optimized Two-Step Etching Process

Pao-Chuan Shih (pcshih@mit.edu) and Tomás Palacios

As EE engineers,
What can we do?

Green energy



<https://doi.org/10.1002/anie.201912844>

Solar-induced
 H_2 fuel generation

GaN

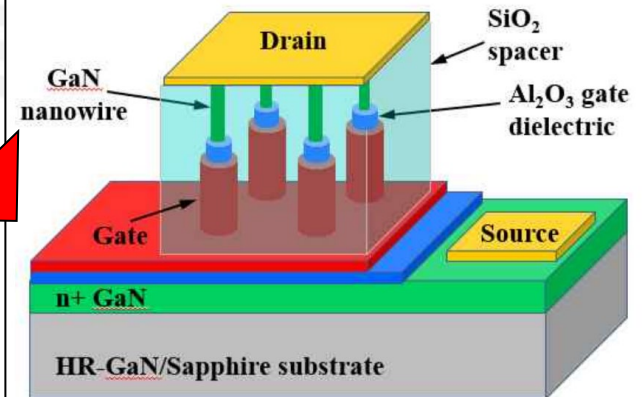
Micro LED



$\frac{1}{100}$

<https://www.cnet.com/tech/home-entertainment/wall-sized-million-dollar-microled-tvs-point-to-the-future-of-television/>

Efficient micro-LEDs



[10.1109/DRC.2015.7175539](https://doi.org/10.1109/DRC.2015.7175539)

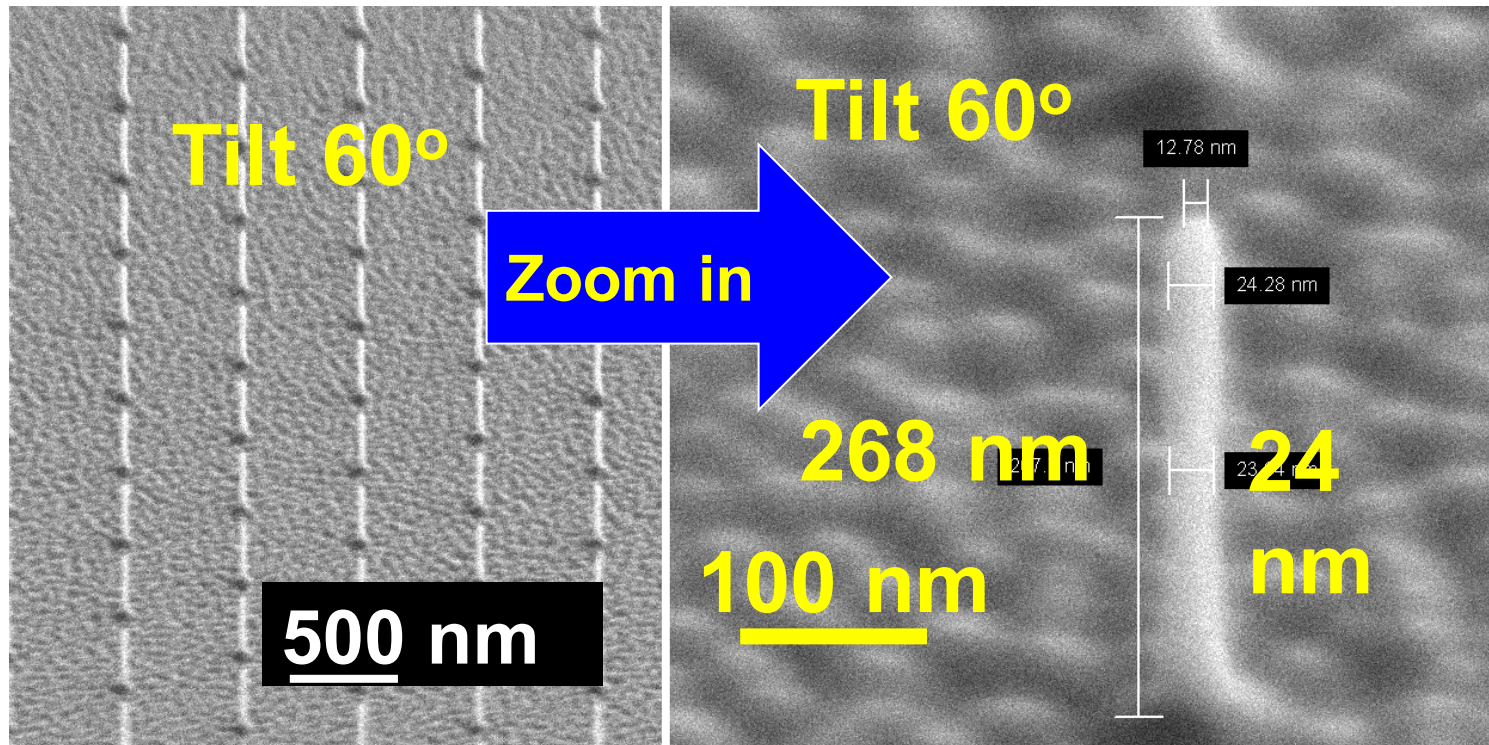
Power electronics

Uniform High-Aspect-Ratio GaN Vertical Sub-30-nm-Diameter Nanowires Formed by Optimized Two-Step Etching Process

Pao-Chuan Shih (pcshih@mit.edu) and Tomás Palacios

To achieve these...

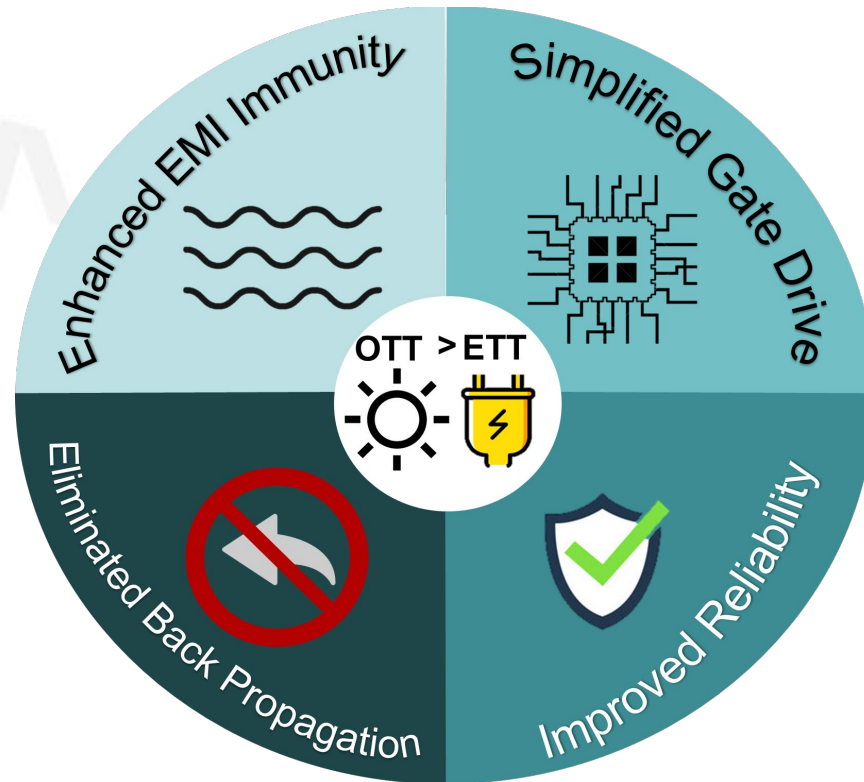
Technologies to form uniform GaN nanostructures is critical



Optically Controlled Vertical GaN Power finFET

Jung-Han Hsia, Kevin Limanta, Joshua Perozek, Richard Molnar
and Tomás Palacios

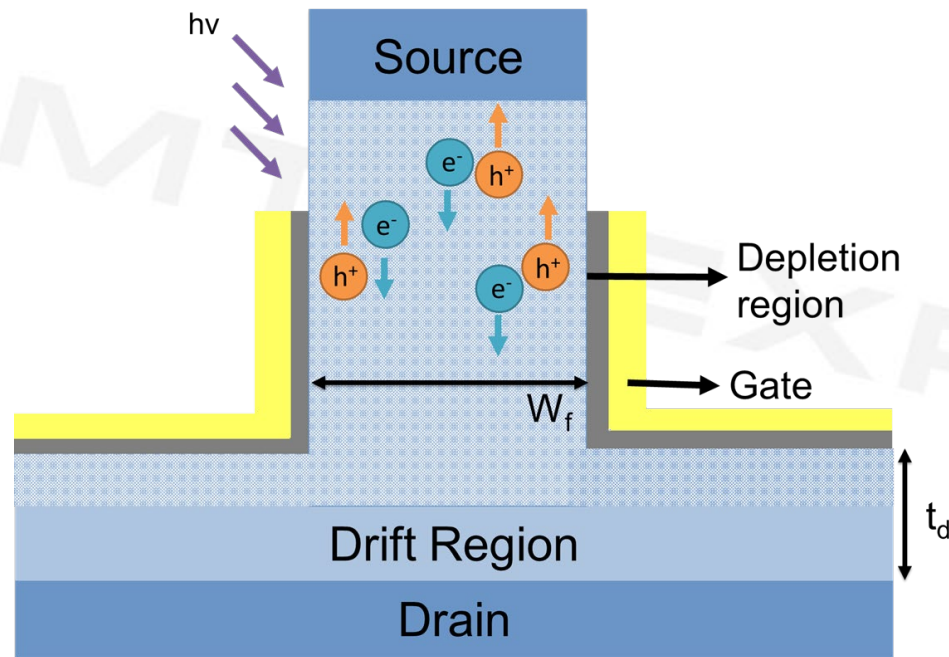
Sponsor: Office of Naval Research



Optically Controlled Vertical GaN Power finFET

Jung-Han Hsia, Kevin Limanta, Joshua Perozek, Richard Molnar
and Tomás Palacios

Sponsor: Office of Naval Research



* Not drawn to scale

Optically Controlled Vertical GaN Power finFET

Jung-Han Hsia, Kevin Limanta, Joshua Perozek, Richard Molnar
and Tomás Palacios

Sponsor: Office of Naval Research

Smart Grid



Electric Vehicle



Pulsed Power



S3.6 Chamber Design of a Portable Breathalyzer for Disease Diagnosis

D. Morales, M. Xue, T. Palacios

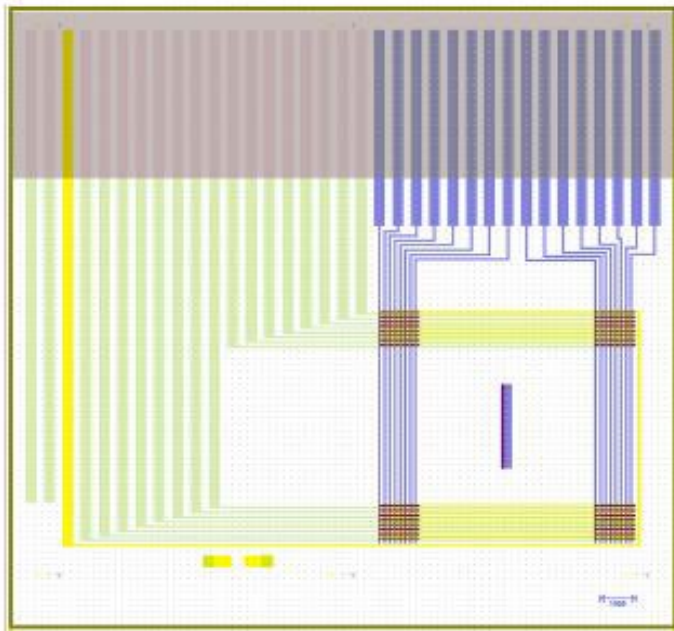
Patient

Breath

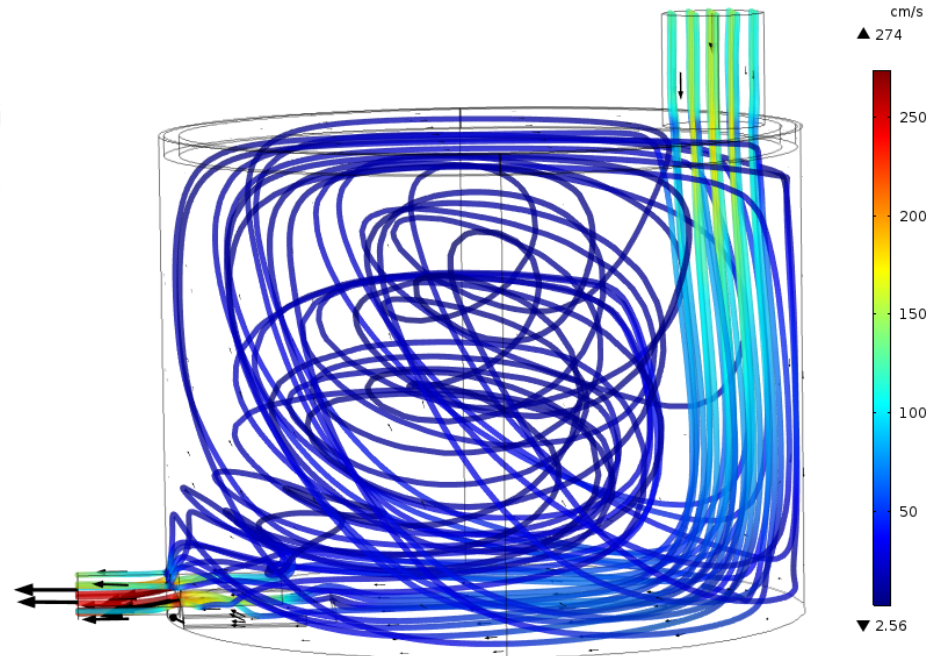
Device

Processing

Diagnosis



Sensor to analyze the volatile organic compounds



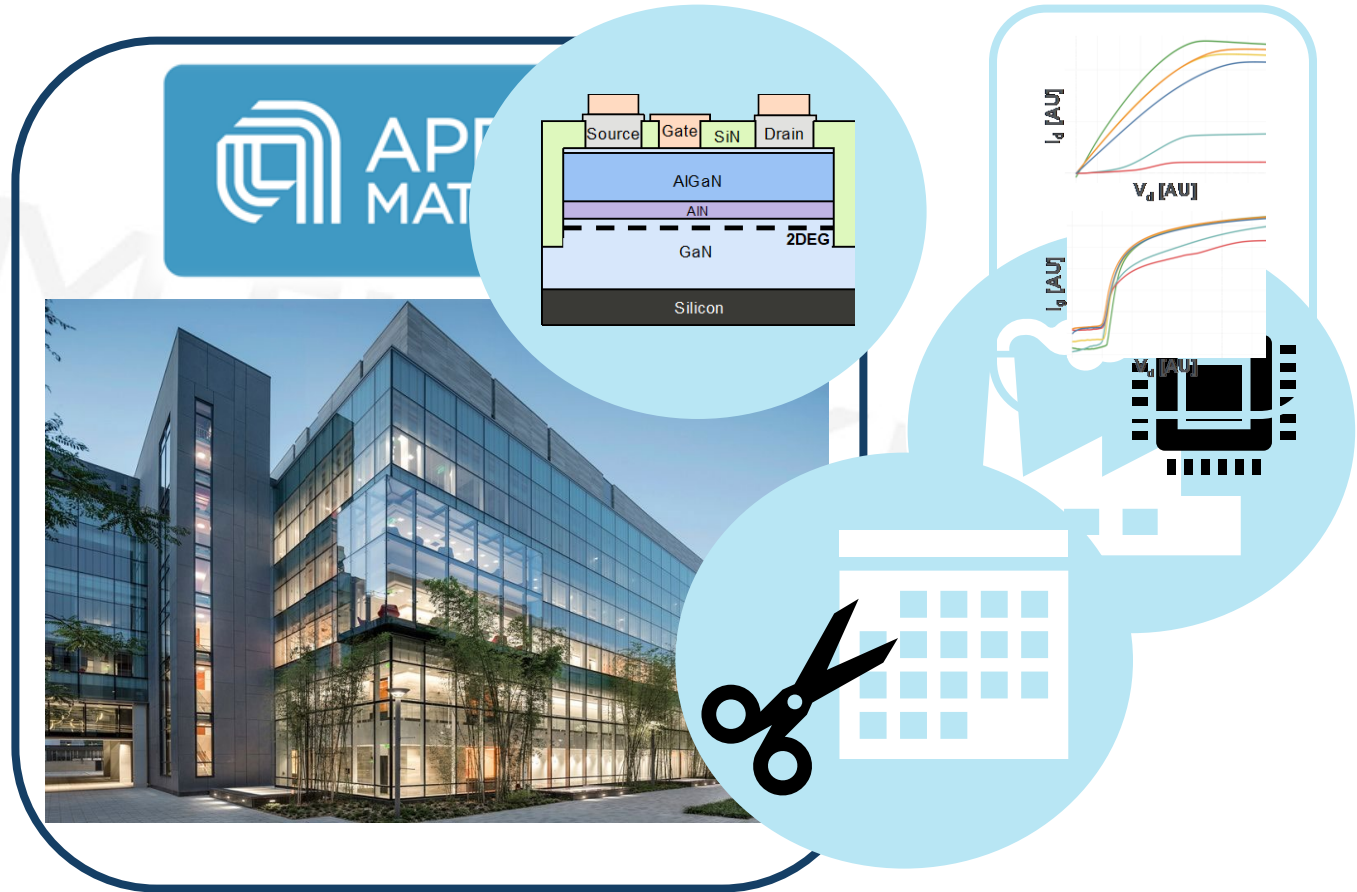
Fluid mechanics simulations

Integration and Evaluation of SiN and Al₂O₃ as Passivation and Gate-dielectrics in GaN HEMTs

G. Micale^{1,2}, R. Ley², T. Palacios¹, B. Briggs²

¹Microsystems Technology Laboratories, MIT

²Applied Materials

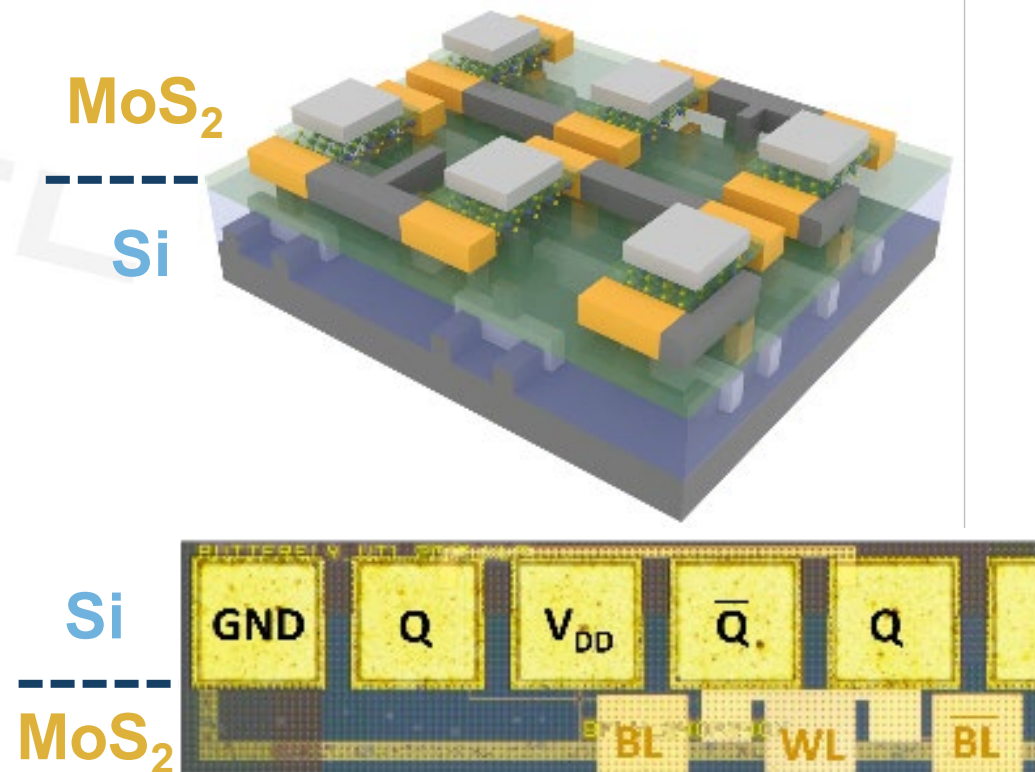


Low-temperature Synthesis of Monolayer MoS₂ on 200-mm Silicon Platform

Jiadi Zhu, Ji-Hoon Park, Steven A. Vitale, Jiangtao Wang, Mohamed Mohamed, Tianyi Zhang, Mantian Xue, Xudong Zheng, Zhien Wang, Jing Kong, Tomás Palacios

Growth @ 275 °C

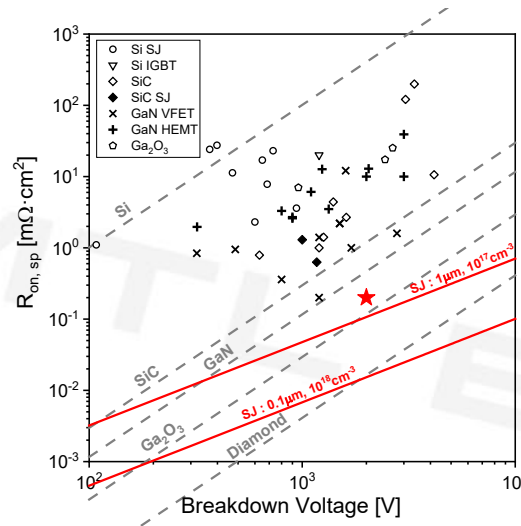
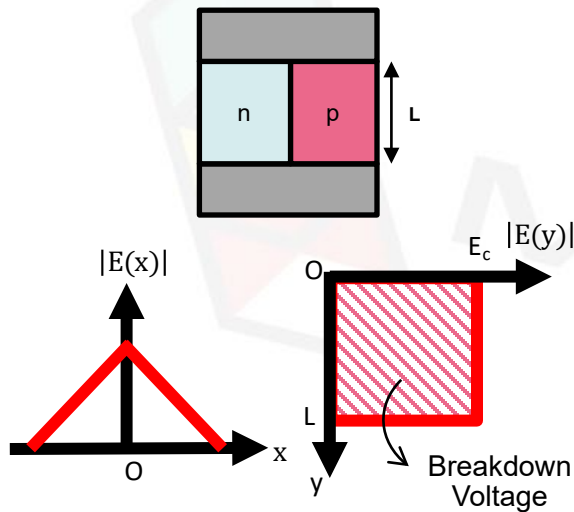
MoS₂ on Si CMOS circuit



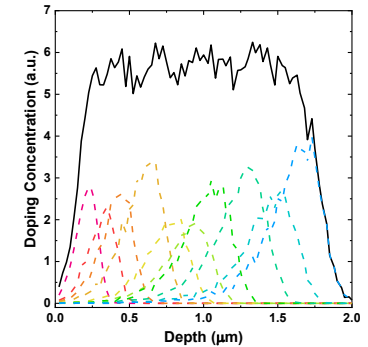
Use of Ion Implantation to Engineer the Electric Field Profiles in GaN Superjunctions

Minsik Oh, Prof. Tomas Palacios

GaN Superjunction Devices

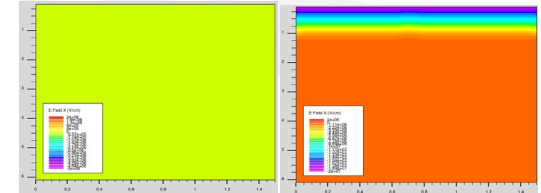


Ion Implantation Simulation

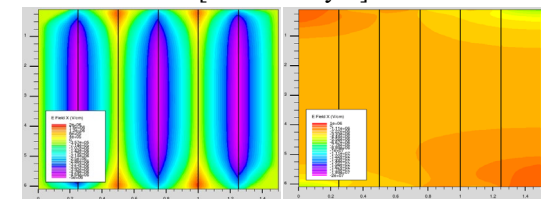


E-field Profile Simulation

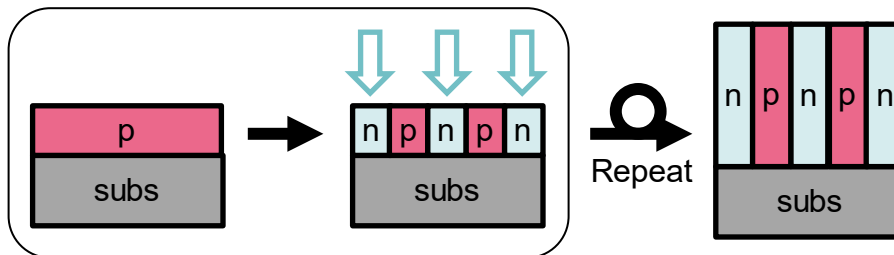
[N-type Drift Layer]



[SJ Drift Layer]

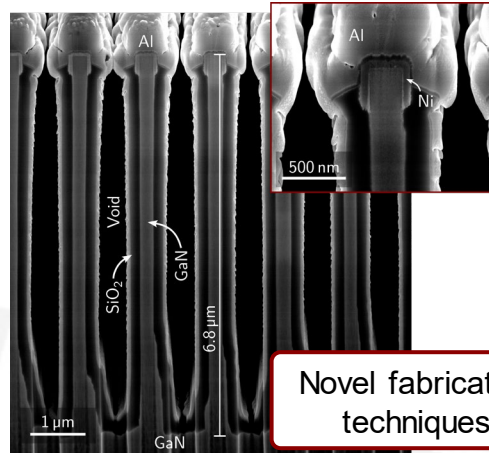
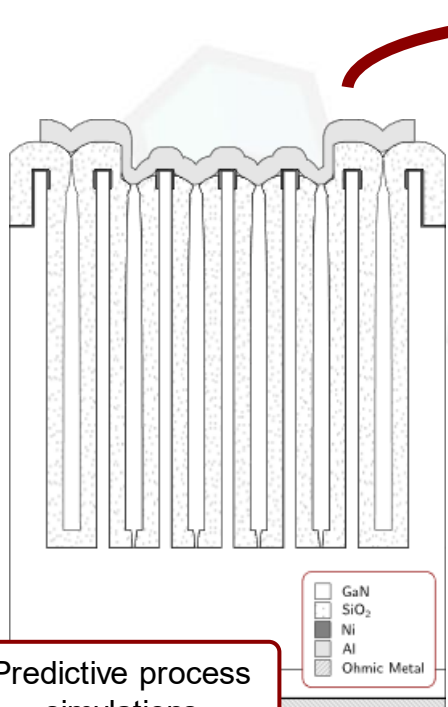


Multiepitaxy & Ion Implantation

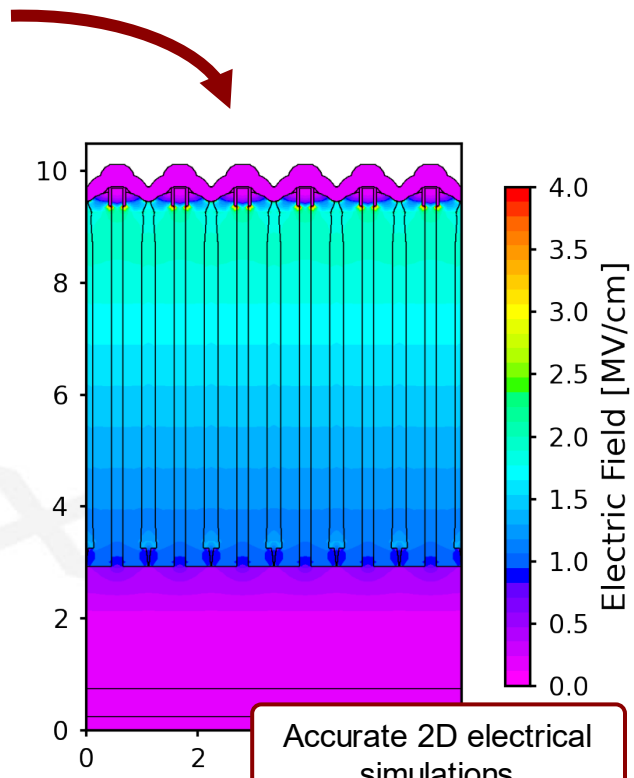
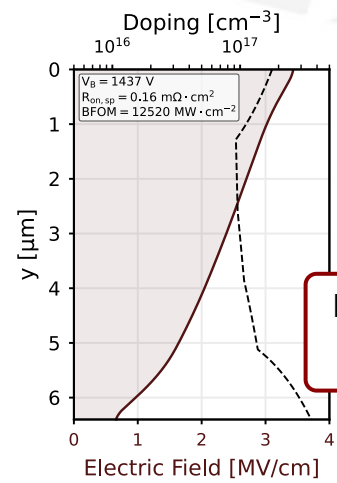
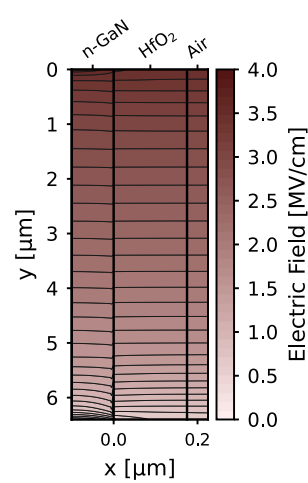


Vertical GaN Superjunctions

Joshua Perozek and Tomás Palacios



Novel fabrication techniques



Accurate 2D electrical simulations

Robust design optimization

High-power AlGaN finFET for mm-Wave applications

Hridibrata Pal, Pao-Chuan Shih, Tomás Palacios, hpal@mit.edu

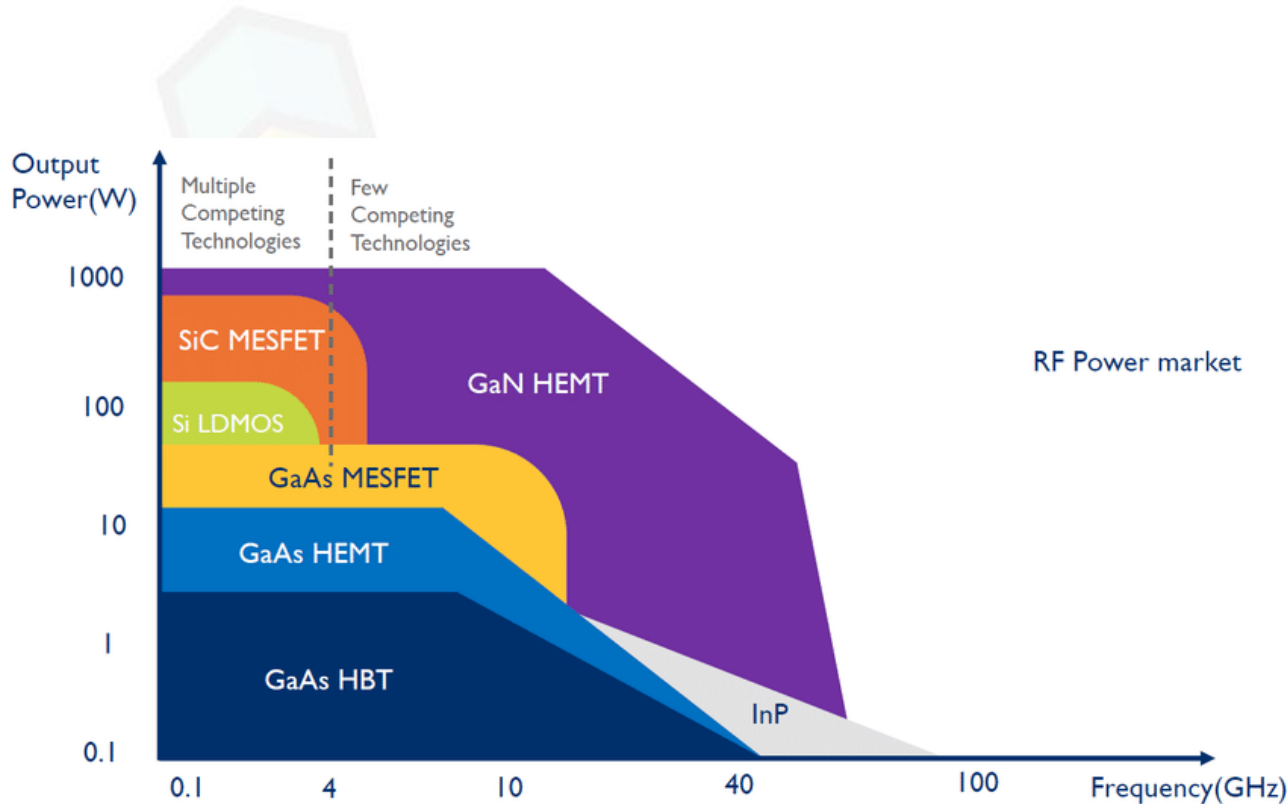


How can it
be achieved?

Efficient power
amplifier is the key

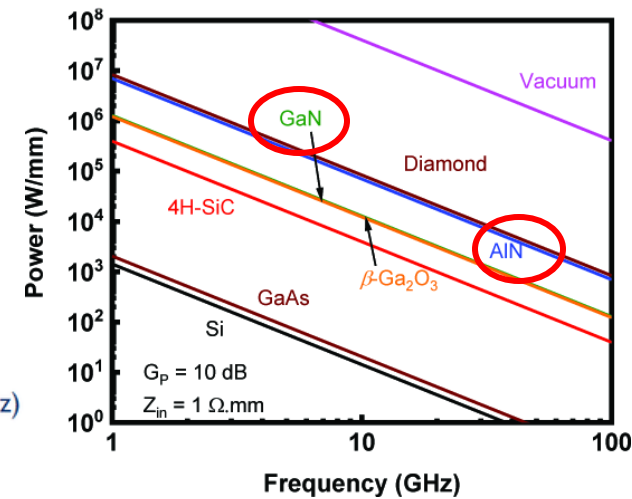
High-power AlGaN finFET for mm-wave applications

Hridibrata Pal, Pao-Chuan Shih, Tomás Palacios, hpal@mit.edu



Next hero
semiconductor

High Al-AlGaN



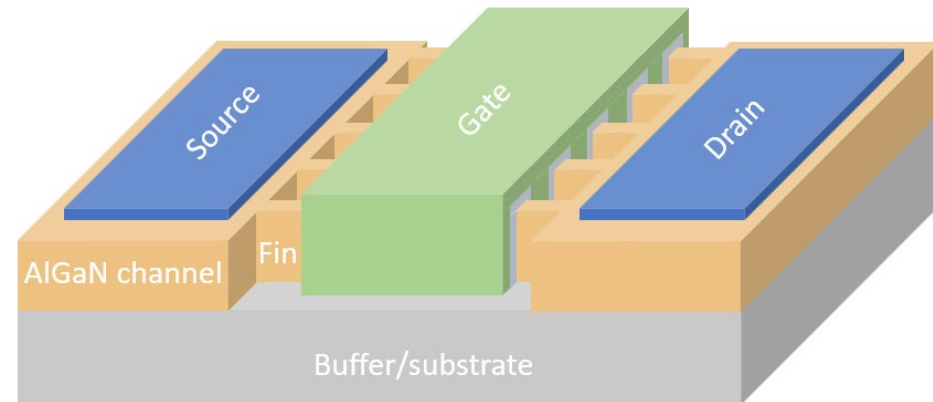
High-power AlGaN finFET for mm-wave applications

Hridibrata Pal, Pao-Chuan Shih, Tomás Palacios, hpal@mit.edu

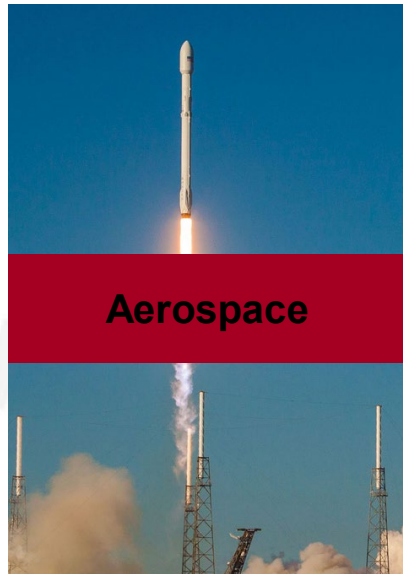
$\text{Al}_{0.7}\text{Ga}_{0.3}\text{N}$ finFET with high aspect ratio fins



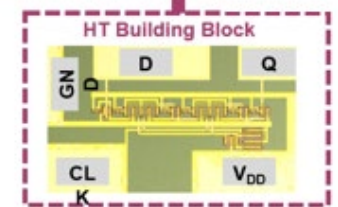
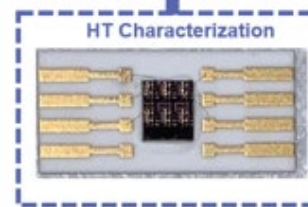
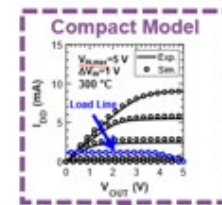
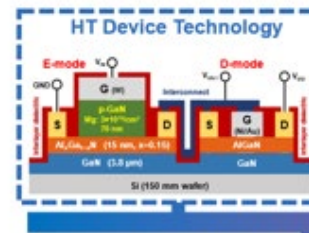
higher power density



Robust High Temperature Electronics with AlGaN/GaN HEMT Technologies



Require digital, power, and RF electronics working at 500° C and beyond!





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Congratulations !!
We are SiMpLy Awesome!!